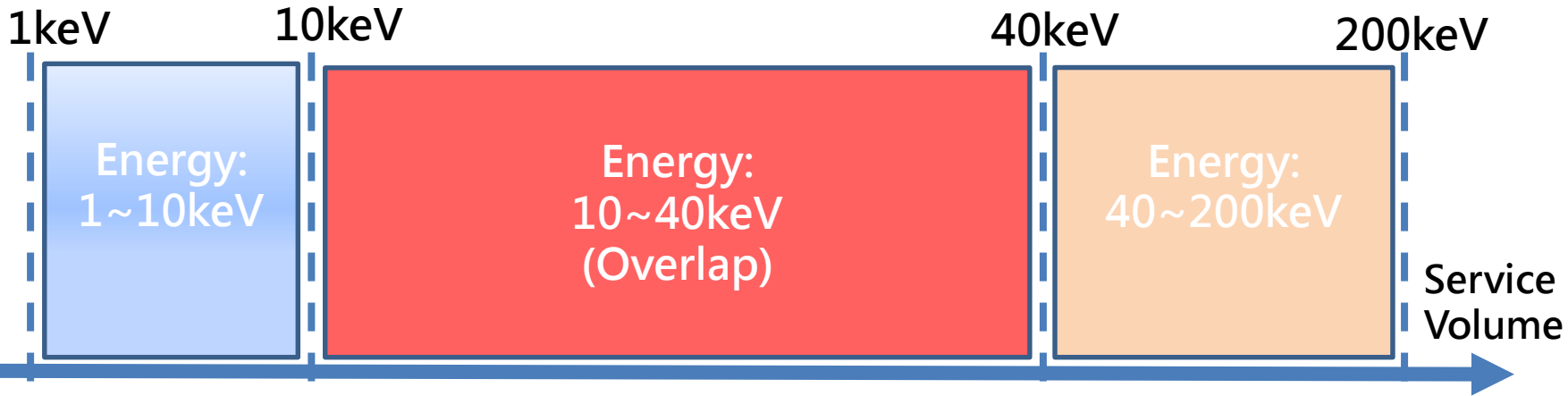


Comprehensive Ion Implanter Service

Comprehensive Ion Implanter Service - Standard Processes



Integration of legacy and new implanters into a comprehensive ion implantation service

Common Ions (B, BF₂, P, As)

1. Energy: 1~<10 keV; Dose: 5E14~1E16 (Note 1); Wafer size: 12~6 inch.
2. Energy: 10~40keV; Dose: 1E12~1E16 (Note 2); Wafer size: 12~4 inch, broken wafers (mounted).
3. Energy: > 40~200keV; Dose: 1E12~5E15; Wafer size: 8~4 inch, broken wafers (mounted).

Special Ions (Si, Ar, C, N)

Energy: 10~200keV; Dose: 1E12~5E15; Wafer size supported: 8~4 inch, broken wafers (mounted).

After submission, process service staff will arrange for implantation on available tools to maximize throughput.

Note 1: For energy 1~5 keV, the maximum dose is 5E15

Note 2: For 12-inch wafers, the supported dose range is 5E14~1E16